

In the Claims:

1. - 27. (Cancelled)

28. (Withdrawn) The method according to claim ~~27~~ 50, wherein the metal area of said metallization being bonded with the ceramic layer by means of direct copper bond bonding or an active soldering process.

29. (Cancelled)

30. (Withdrawn) The method according to claim 27, wherein the at least one metal area is produced using the Mo-Mn process, a W process, an LTCC process, or a combination thereof.

31. (Currently amended) The method according to claim ~~27~~ 50, wherein the heating of the ceramic layer during the thermal treatment ~~or process step~~ is effected by means of an energy beam or a laser beam.

32. (Currently amended) The method according to claim 31, wherein the laser beam is focused in order to form an oval focus, with its greater cross-section axis oriented in the processing direction ~~(A)~~.

33. (Withdrawn) The method according to claim 27, wherein the ceramic layer is thermally separated or split along the respective separating line by means of the thermal treatment or process step.

34. (Currently amended) The method according to claim ~~27~~ 50, wherein a break-off line is produced in the ceramic layer by means of the thermal treatment ~~or process-step~~, enabling subsequent controlled mechanical breaking of the ceramic layer.

35. (Withdrawn) The method according to claim 27, wherein the heating of the ceramic layer is effected by means of a hot gas beam, a flame, a plasma, or microwave energy.

36. (Currently amended) The method according to claim ~~27~~ 50, wherein the cooling of the ceramic layer is effected progressively at a pre-defined spatial and/or temporal distance (Δ) from the heating.

37. (Currently amended) The method according to claim ~~27~~ 36, wherein the ~~treatment~~ cooling of the ceramic layer is effected with the coolant progressively and point by point.

38. (Currently amended) The method according to claim 37, wherein the coolant is applied to the ceramic layer in the form of at least one coolant stream.

39. (Currently amended) The method according to claim 37, wherein the coolant is a liquid medium, water, a gaseous or vaporous medium, an aerosol, or a mixture of these.

40. (Withdrawn) The method according to claim 27, wherein the ceramic layer is held in a clamping fixture during the thermal treatment or process step, by means of a vacuum.

41. (Currently amended) The method according to claim ~~27~~ 50, wherein the ceramic layer or the metal-ceramic substrate formed by said layer is located on a self-adhesive foil for separation into single substrates.

42. (Currently amended) The method according to claim ~~27~~ 50, wherein the thermal treatment is effected along a groove produced on at least one surface side of the ceramic layer.

43. (Currently amended) The method according to claim ~~27~~ 50, wherein at least one metal area is applied to both surface sides of the ceramic layer.

44. (Currently amended) The method according to claim ~~27~~ 50, wherein the ceramic layer is part of a multiple substrate, that a plurality of metal areas, each allocated to one single substrate, are provided on at least one surface side of the ceramic layer, and that the separating or break-off lines are produced between the single substrates through the thermal treatment ~~or process step~~.

45. (Currently amended) The method according to claim 27 50, wherein the ceramic layer is selected from the mullite group, Al_2O_3 , Al_2O_3 , AlN , Si_3N_4 , SiC , BeO , TiO_2 , ZrO_2 , or Al_2O_3 , Al_2O_3 with a ZrO_2 content.

46. (Currently amended) The method according to claim 27 50, wherein the ceramic layer has a thickness between 0.1 and 3 mm.

47. (Currently amended) The method according to claim 27 50, wherein the at least one metal area has a thickness between 0.02 and 0.6 mm, or a thickness between 0.1 and 0.6 mm.

48. (Currently amended) The method according to claim 27 50, wherein in the case of a plurality of metal areas on one surface side of the ceramic layer, said metal areas are at a distance of 0.1 – 3 mm from each other.

49. (Withdrawn) The method according to one claim 27, wherein the metal areas are manufactured at least partially from a metal layer or foil, a copper layer or foil, using a direct bonding process or an active soldering process.

50. (New) A method for manufacturing a metal-ceramic substrate, said method comprising the steps of:

- a. applying a metallization to at least one surface side of a ceramic layer,
- b. structuring the metallization into a plurality of individual metal areas such that the metal areas on the at least one surface side of the ceramic layer are at a distance from another,
- c. progressively heating only the ceramic layer in a thermal treatment process in areas in between the metal areas and progressively shock-cooling the ceramic layer to produce separating or break of lines in between the metal areas by controlled fracture or weakening the material in the ceramic layer,

wherein the heating of the ceramic layer during the thermal treatment process takes place without vaporization or burning off the ceramic material in a treatment area that moves in relation to the ceramic layer.

51. (New) A method for manufacturing a metal-ceramic substrate, said method comprising the steps of:

- d. applying a metallization to at least one surface side of a ceramic layer,
- e. structuring the metallization into a plurality of individual metal areas such, that the metal areas on the at least one surface side of the ceramic layer are at a distance from another,
- f. progressively heating only the ceramic layer in a thermal treatment process in the areas in between all the metal areas and progressively shock-cooling the ceramic layer to produce separating or break of lines in between all metal areas by controlled fracture or weakening the material in the ceramic layer,

wherein the heating of the ceramic layer during the thermal treatment process takes place without vaporization or burning off the ceramic material in a treatment area that moves in relation to the ceramic layer, wherein the ceramic layer has a thickness between 0.1 and 3 mm, and wherein the metal areas have a thickness between 0.02 and 0.6 mm and are at a distance of 0.1 – 3 mm from each other.